

David Cameron

List of Publications by Year in Descending Order

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The third column is the impact factor (IF) of the journal, and the fourth column is the number of citations of the article.

129
papers

3,810
citations

31
h-index

57
g-index

138
ext. papers

4,058
ext. citations

3.4
avg, IF

5.21
L-index

#	Paper	IF	Citations
129	White paper on the future of plasma science and technology in plastics and textiles. <i>Plasma Processes and Polymers</i> , 2019 , 16, 1700228	3.4	51
128	Ellipsometry, reflectance, and photoluminescence of nanocrystalline CuCl thin films on silicon. <i>Journal of Vacuum Science and Technology B: Nanotechnology and Microelectronics</i> , 2019 , 37, 051206	1.3	
127	Comparison of ALD coated nanofiltration membranes to unmodified commercial membranes in mine wastewater treatment. <i>Separation and Purification Technology</i> , 2018 , 192, 69-77	8.3	31
126	Structural and Optical Properties of Luminescent Copper(I) Chloride Thin Films Deposited by Sequentially Pulsed Chemical Vapour Deposition. <i>Coatings</i> , 2018 , 8, 369	2.9	6
125	Catalytic Performance of Ag ₂ O and Ag Doped CeO ₂ Prepared by Atomic Layer Deposition for Diesel Soot Oxidation. <i>Coatings</i> , 2018 , 8, 237	2.9	16
124	Controlled fabrication and electrowetting properties of silicon nanostructures. <i>Journal of Adhesion Science and Technology</i> , 2017 , 31, 31-40	2	3
123	Surface chemistry and initial growth of Al ₂ O ₃ on plasma modified PTFE studied by ALD. <i>Surfaces and Interfaces</i> , 2017 , 6, 223-228	4.1	7
122	Surface modification of acetaminophen particles by atomic layer deposition. <i>International Journal of Pharmaceutics</i> , 2017 , 525, 160-174	6.5	31
121	Hafnium oxide thin films as a barrier against copper diffusion in solar absorbers. <i>Solar Energy Materials and Solar Cells</i> , 2017 , 166, 140-146	6.4	9
120	Ambient air plasma pre-treatment of non-woven fabrics for deposition of antibacterial poly (l-lactide) nanoparticles. <i>Plasma Processes and Polymers</i> , 2017 , 14, 1600231	3.4	12
119	Review Article: Recommended reading list of early publications on atomic layer deposition Outcome of the Virtual Project on the History of ALD <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2017 , 35, 010801	2.9	55
118	Atomic layer deposition of nanocrystallite arrays of copper(I) chloride for optoelectronic structures. <i>Journal of Materials Science: Materials in Electronics</i> , 2017 , 28, 11695-11701	2.1	3
117	Atomic layer deposition-A novel method for the ultrathin coating of minitables. <i>International Journal of Pharmaceutics</i> , 2017 , 531, 47-58	6.5	13
116	Atomic layer deposition of cerium oxide for potential use in diesel soot combustion. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2016 , 34, 031506	2.9	7
115	Measuring optical anisotropy in poly(3,4-ethylene dioxythiophene):poly(styrene sulfonate) films with added graphene. <i>Organic Electronics</i> , 2015 , 25, 317-323	3.5	14
114	Nucleation and initial growth of atomic layer deposited titanium oxide determined by spectroscopic ellipsometry and the effect of pretreatment by surface barrier discharge. <i>Applied Surface Science</i> , 2015 , 345, 216-222	6.7	9
113	Spatial atomic layer deposition: Performance of low temperature H ₂ O and O ₃ oxidant chemistry for flexible electronics encapsulation. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 031603	2.9	19

112	Low temperature temporal and spatial atomic layer deposition of TiO ₂ films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2015 , 33, 041512	2.9	30
111	Mechanical properties of atomic layer deposited Al ₂ O ₃ /ZnO nanolaminates. <i>Surface and Coatings Technology</i> , 2015 , 284, 198-205	4.4	15
110	Attachment of Poly(l-lactide) Nanoparticles to Plasma-Treated Non-Woven Polymer Fabrics Using Inkjet Printing. <i>Macromolecular Bioscience</i> , 2015 , 15, 1274-82	5.5	8
109	Comparison of direct and indirect plasma oxidation of NO combined with oxidation by catalyst. <i>Fuel</i> , 2015 , 144, 137-144	7.1	39
108	Roll-to-roll atomic layer deposition process for flexible electronics encapsulation applications. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2014 , 32, 051603	2.9	46
107	Influence of substrate contamination, web handling, and pretreatments on the barrier performance of aluminum oxide atomic layer-deposited BOPP film 2014 , 11, 775-784		10
106	UV protective zinc oxide coating for biaxially oriented polypropylene packaging film by atomic layer deposition. <i>Thin Solid Films</i> , 2014 , 570, 33-37	2.2	13
105	Enhancement of Atmospheric Plasma Decomposition of Toluene Using Porous Dielectric Conformally Coated with Titanium Dioxide by Atomic Layer Deposition. <i>Science of Advanced Materials</i> , 2014 , 6, 2098-2105	2.3	3
104	Protecting BOPP film from UV degradation with an atomic layer deposited titanium oxide surface coating. <i>Applied Surface Science</i> , 2013 , 282, 506-511	6.7	10
103	Zinc release from atomic layer deposited zinc oxide thin films and its antibacterial effect on Escherichia coli. <i>Applied Surface Science</i> , 2013 , 287, 375-380	6.7	26
102	Fundamentals of Atomic Layer Deposition 2013 , 1-31		2
101	Oxide films 2013 , 67-159		
100	Organic and Hybrid Materials 2013 , 207-213		
99	ALD Applications and Industry 2013 , 215-242		5
98	(Invited) Molecular Layer Deposition. <i>ECS Transactions</i> , 2013 , 58, 263-275	1	6
97	Nitrogen doping in atomic layer deposition grown titanium dioxide films by using ammonium hydroxide. <i>Thin Solid Films</i> , 2012 , 526, 212-217	2.2	8
96	Molecular layer deposition of polyethylene terephthalate thin films. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A121	2.9	34
95	The importance of the majority carrier polarity and p-n junction in titanium dioxide films to their photoactivity and photocatalytic properties. <i>Surface Science</i> , 2012 , 606, L22-L25	1.8	10

94	Spatial atomic layer deposition: A route towards further industrialization of atomic layer deposition. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 010802	2.9	248
93	Adhesion of extrusion-coated polymer sealing layers to a fiber-based packaging material with an atomic layer deposited aluminum oxide surface coating. <i>Polymer Engineering and Science</i> , 2012 , 52, 1985-1990	2.3	10
92	Continuous atomic layer deposition: Explanation for anomalous growth rate effects. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A122	2.9	22
91	Nanoscratch testing of atomic layer deposition and magnetron sputtered TiO ₂ and Al ₂ O ₃ coatings on polymeric substrates. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2012 , 30, 01A132	2.9	10
90	Surface modification of polymers by plasma-assisted atomic layer deposition. <i>Surface and Coatings Technology</i> , 2011 , 205, S475-S479	4.4	20
89	An atomic layer deposition process for moving flexible substrates. <i>Chemical Engineering Journal</i> , 2011 , 171, 345-349	14.7	54
88	Chemical and microstructural modifications in LiPON thin films exposed to atmospheric humidity. <i>Solid State Ionics</i> , 2011 , 185, 47-51	3.3	26
87	Utilisation of continuous atomic layer deposition process for barrier enhancement of extrusion-coated paper. <i>Surface and Coatings Technology</i> , 2011 , 205, 3916-3922	4.4	38
86	Atomic layer deposition on polymer based flexible packaging materials: Growth characteristics and diffusion barrier properties. <i>Thin Solid Films</i> , 2011 , 519, 3146-3154	2.2	54
85	Atomic layer deposition of CuCl nanoparticles. <i>Applied Physics Letters</i> , 2010 , 97, 241905	3.4	9
84	Ion fluxes in medium frequency pulsed DC magnetron sputtering. <i>Surface and Coatings Technology</i> , 2010 , 204, 3131-3134	4.4	4
83	Atomic layer deposition of tin dioxide sensing film in microhotplate gas sensors. <i>Sensors and Actuators B: Chemical</i> , 2010 , 148, 227-232	8.5	22
82	Performance of RC and PES ultrafiltration membranes in filtration of pulp mill process waters. <i>Desalination</i> , 2010 , 264, 249-255	10.3	41
81	Interaction of Plasma Deposited HMDSO-Based Coatings with Fibrinogen and Human Blood Plasma: The Correlation between Bulk Plasma, Surface Characteristics and Biomolecule Interaction. <i>Plasma Processes and Polymers</i> , 2010 , 7, 411-421	3.4	18
80	Effect of pulse frequency on the ion fluxes during pulsed dc magnetron sputtering. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2009 , 27, 282-286	2.9	7
79	Atomic layer deposited TiO ₂ films in photodegradation of aqueous salicylic acid. <i>Separation and Purification Technology</i> , 2009 , 66, 130-134	8.3	44
78	Influence of oxygen depletion layer on the properties of tin oxide gas-sensing films fabricated by atomic layer deposition. <i>Applied Physics A: Materials Science and Processing</i> , 2009 , 95, 621-627	2.6	10
77	Adhesion of Ti and TiC Coatings on PMMA Subject to Plasma Treatment: Effect of Intermediate Layers of Al ₂ O ₃ and TiO ₂ Deposited by Atomic Layer Deposition. <i>Plasma Processes and Polymers</i> , 2009 , 6, 631-641	3.4	46

76	Plasma-Assisted Atomic Layer Deposition of Al ₂ O ₃ at Room Temperature. <i>Plasma Processes and Polymers</i> , 2009 , 6, S237-S241	3-4	44
75	Titanium dioxide thin films, their structure and its effect on their photoactivity and photocatalytic properties. <i>Thin Solid Films</i> , 2009 , 517, 6666-6670	2.2	61
74	Temperature dependent optical properties of UV emitting β CuCl thin films. <i>Thin Solid Films</i> , 2008 , 516, 1439-1442	2.2	5
73	Morphological, optical and electrical properties of β CuCl deposited by vacuum evaporation. <i>Journal of Materials Science: Materials in Electronics</i> , 2008 , 19, 99-101	2.1	3
72	Electrical studies on sputtered CuCl thin films. <i>Journal of Materials Science: Materials in Electronics</i> , 2008 , 19, 103-106	2.1	4
71	Optical properties of CuCl films on silicon substrates. <i>Physica Status Solidi (B): Basic Research</i> , 2008 , 245, 2808-2814	1.3	6
70	Influence of target to substrate distance on the sputtered CuCl film properties. <i>Thin Solid Films</i> , 2008 , 516, 5531-5535	2.2	6
69	A Comparative Study of Characteristics of SiO _x CyHz, TiO _x and SiO-TiO Oxide-Based Biocompatible Coatings. <i>Plasma Processes and Polymers</i> , 2007 , 4, S369-S373	3-4	12
68	Characterisation of n-type β CuCl on Si for UV optoelectronic applications. <i>Journal of Materials Science: Materials in Electronics</i> , 2007 , 18, 57-60	2.1	5
67	Evaluation of the chemical, electronic and optoelectronic properties of β CuCl thin films and their fabrication on Si substrates. <i>Journal Physics D: Applied Physics</i> , 2007 , 40, 3461-3467	3	12
66	Growth of CuCl thin films by magnetron sputtering for ultraviolet optoelectronic applications. <i>Journal of Applied Physics</i> , 2006 , 100, 033520	2.5	33
65	Encapsulation of the heteroepitaxial growth of wide band gap β CuCl on silicon substrates. <i>Journal of Crystal Growth</i> , 2006 , 287, 112-117	1.6	16
64	Impact on structural, optical and electrical properties of CuCl by incorporation of Zn for n-type doping. <i>Journal of Crystal Growth</i> , 2006 , 287, 139-144	1.6	17
63	On the ion flux and energy gain during pulsed DC operation of an opposed target magnetron. <i>Surface and Coatings Technology</i> , 2006 , 200, 5306-5317	4-4	13
62	A three-step algorithm for solving 2D inverse magnetostatic problems for magnetron design applications. <i>Inverse Problems in Science and Engineering</i> , 2005 , 13, 279-297	1.3	1
61	Optical properties of DLC films deposited by the saddle field fast atom neutral beam source. <i>Journal of Materials Processing Technology</i> , 2005 , 169, 219-222	5-3	11
60	Comparison of the operating characteristics of an opposed target magnetron using ferromagnetic and non-ferromagnetic targets. <i>Surface and Coatings Technology</i> , 2005 , 200, 644-648	4-4	3
59	PECVD of biocompatible coatings on 316L stainless steel. <i>Surface and Coatings Technology</i> , 2005 , 200, 1031-1035	4-4	37

58	Growth and characterisation of wide-bandgap, I-VII optoelectronic materials on silicon. <i>Journal of Materials Science: Materials in Electronics</i> , 2005 , 16, 415-419	2.1	19
57	The use of wide-bandgap CuCl on silicon for ultra-violet photonics 2005 ,		1
56	Optical investigations on sputtered CuCl thin films. <i>Materials Research Society Symposia Proceedings</i> , 2005 , 891, 1		1
55	Pulsed dc operation of a Penning-type opposed target magnetron. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2005 , 23, 66-71	2.9	10
54	Room-temperature ultraviolet luminescence from β -CuCl grown on near lattice-matched silicon. <i>Journal of Applied Physics</i> , 2005 , 98, 113512	2.5	28
53	The characteristics of thin film electroluminescent displays produced using sol-gel produced tantalum pentoxide and zinc sulfide. <i>Thin Solid Films</i> , 2004 , 447-448, 85-89	2.2	49
52	Effect of surface treatment on the adhesion of DLC film on 316L stainless steel. <i>Surface and Coatings Technology</i> , 2003 , 163-164, 541-545	4.4	57
51	Optical and electronic properties of carbon nitride. <i>Surface and Coatings Technology</i> , 2003 , 169-170, 245-250	4.4	31
50	DLC films deposited by a neutral beam source: adhesion to biological implant metals. <i>Surface and Coatings Technology</i> , 2003 , 169-170, 254-257	4.4	8
49	Pre-treatment of substrates for improved adhesion of diamond-like carbon films on surgically implantable metals deposited by saddle field neutral beam source. <i>Surface and Coatings Technology</i> , 2003 , 174-175, 579-583	4.4	15
48	Stress and adhesion in DLC coatings on 316L stainless steel deposited by a neutral beam source. <i>Journal of Materials Processing Technology</i> , 2003 , 141, 127-131	5.3	27
47	Investigation of annealing effects on sol-gel deposited indium tin oxide thin films in different atmospheres. <i>Thin Solid Films</i> , 2002 , 420-421, 76-82	2.2	133
46	Preparation and Characterization of TiO ₂ Thin Films by Sol-Gel Method. <i>Journal of Sol-Gel Science and Technology</i> , 2002 , 25, 137-145	2.3	113
45	Structural variations in CrN/NbN superlattices. <i>Surface and Coatings Technology</i> , 2001 , 142-144, 567-572	4.4	30
44	Characterization of transparent conductive ITO thin films deposited on titanium dioxide film by a sol-gel process. <i>Surface and Coatings Technology</i> , 2001 , 142-144, 776-780	4.4	65
43	Preparation and properties of transparent conductive aluminum-doped zinc oxide thin films by sol-gel process. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 2001 , 19, 1642-1646	2.9	137
42	Zinc sulfide thin films produced by sulfidation of sol-gel deposited zinc oxide. <i>Thin Solid Films</i> , 2001 , 398-399, 24-28	2.2	34
41	The effect of nitrogen partial pressure on the bonding in sputtered CN _x films: implications for formation of β -C ₃ N ₄ . <i>Surface and Coatings Technology</i> , 2000 , 131, 488-492	4.4	12

40	Optical and electrical properties of transparent conductive ITO thin films deposited by sol-gel process. <i>Thin Solid Films</i> , 2000 , 377-378, 455-459	2.2	241
39	Penning type magnetron sputtering source and its use in the production of carbon nitride coatings. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1999 , 17, 62-69	2.9	9
38	Evidence for continuous areas of crystalline CN_x in sputter-deposited thin films. <i>Journal of Materials Research</i> , 1999 , 14, 2359-2363	2.5	30
37	Electrical properties of reactively sputtered CN_x films. <i>Thin Solid Films</i> , 1999 , 341, 94-100	2.2	34
36	Bonding structure in carbon nitride films: variation with nitrogen content and annealing temperature. <i>Surface and Coatings Technology</i> , 1999 , 112, 133-139	4.4	52
35	Electrical properties of reactively sputtered carbon nitride films. <i>Surface and Coatings Technology</i> , 1999 , 116-119, 54-58	4.4	12
34	Adhesion of carbon nitride thin films on tool steel. <i>Surface and Coatings Technology</i> , 1999 , 116-119, 46-52	4.4	14
33	Investigation of the valence band states of reactively sputtered carbon nitride films. <i>Thin Solid Films</i> , 1999 , 355-356, 79-84	2.2	16
32	Effect of substrate bias on the bonding structure of carbon nitride thin films. <i>Thin Solid Films</i> , 1999 , 355-356, 85-88	2.2	14
31	Vibrational properties of carbon nitride films by Raman spectroscopy. <i>Thin Solid Films</i> , 1998 , 332, 62-68	2.2	137
30	Properties of Pd/Sn Ohmic contacts on n-GaAs. <i>Journal of Materials Processing Technology</i> , 1998 , 77, 42-49	5.3	3
29	Stress behaviour of reactively sputtered nitrogenated carbon films. <i>Surface and Coatings Technology</i> , 1998 , 98, 985-990	4.4	1
28	The importance of the Pd to Sn ratio and of annealing cycles on the performance of Pd/Sn ohmic contacts to n-GaAs. <i>Thin Solid Films</i> , 1997 , 292, 264-269	2.2	7
27	The composition and bonding structure of CN_x films and their influence on the mechanical properties. <i>Thin Solid Films</i> , 1997 , 308-309, 130-134	2.2	24
26	Thermal stability of the non-alloyed Pd/Sn and Pd/Ge Ohmic contacts to n-GaAs. <i>Thin Solid Films</i> , 1997 , 308-309, 607-610	2.2	4
25	Comparison of Pd/Sn and Pd/Sn/Au Thin-Film Systems for Device Metallization. <i>Materials Research Society Symposia Proceedings</i> , 1996 , 427, 583		3
24	Magnetron sputtering of tin protective coatings for medical applications. <i>Journal of Materials Processing Technology</i> , 1996 , 56, 422-430	5.3	35
23	Effects of Au overlayers on the electrical and morphological characteristics of Pd/Sn ohmic contacts to n-GaAs. <i>Thin Solid Films</i> , 1996 , 290-291, 417-421	2.2	4

22	Electrochemical deposition of prussian blue films across interdigital array electrodes and their use in gas sensing. <i>Electroanalysis</i> , 1996 , 8, 195-198	3	23
21	Electroluminescent zinc sulphide devices produced by sol-gel processing. <i>Thin Solid Films</i> , 1996 , 280, 221-226	2.2	122
20	Magnetic Field in a Commercial Sputter Magnetron. <i>Key Engineering Materials</i> , 1996 , 118-119, 287-294	0.4	
19	Magnetic field in two-dimensional magnetrons. <i>Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films</i> , 1995 , 13, 2151-2156	2.9	4
18	Magnetron-sputtered carbon nitride (CN _x) films. <i>Surface and Coatings Technology</i> , 1995 , 74-75, 696-703	4.4	28
17	Magnetron sputtered carbon nitride films. <i>Surface and Coatings Technology</i> , 1994 , 68-69, 188-193	4.4	14
16	Aluminum-doped zinc oxide transparent conductors deposited by the sol-gel process. <i>Thin Solid Films</i> , 1994 , 238, 83-87	2.2	316
15	Plasma diagnostics in the growth of c-BN films. <i>Diamond and Related Materials</i> , 1994 , 3, 551-554	3.5	7
14	Characterization of mixed-phase BN thin films deposited by plasma CVD. <i>Surface and Coatings Technology</i> , 1993 , 60, 502-505	4.4	21
13	Magnetic fields in magnetron sputtering systems. <i>Surface and Coatings Technology</i> , 1993 , 57, 1-5	4.4	6
12	Properties of mixed-phase BN films deposited by r.f. PACVD. <i>Thin Solid Films</i> , 1993 , 236, 96-102	2.2	20
11	Plasma deposition of hard carbon films as wear protective coatings. <i>Journal of Materials Processing Technology</i> , 1991 , 26, 117-132	5.3	1
10	Plasma deposition of cubic boron nitride films from non-toxic material at low temperatures. <i>Surface and Coatings Technology</i> , 1991 , 49, 416-421	4.4	28
9	The correlation of channel mobility with interface state measurements on InP MOSFET structures. <i>Solid-State Electronics</i> , 1984 , 27, 305-309	1.7	2
8	Factors influencing the performance of InP metal/insulator/semiconductor field effect transistors. <i>Thin Solid Films</i> , 1983 , 103, 61-70	2.2	5
7	Planar self-aligned ion-implanted InP MOSFET. <i>Electronics Letters</i> , 1982 , 18, 534	1.1	12
6	Substrate effects on performance of InP MOSFETs. <i>Electronics Letters</i> , 1982 , 18, 415	1.1	4
5	InP metal/oxide/semiconductor devices incorporating Al ₂ O ₃ dielectrics chemically vapour deposited at low pressure. <i>Thin Solid Films</i> , 1982 , 91, 339-348	2.2	26

4	The deposition of insulators onto InP using plasma-enhanced chemical vapour deposition. <i>Thin Solid Films</i> , 1981 , 85, 61-69	2.2	26
3	MBE-grown fluoride films: A new class of epitaxial dielectrics. <i>Journal of Vacuum Science and Technology</i> , 1981 , 19, 415-420		165
2	The structural and electron transport properties of CdS grown by molecular beam epitaxy. <i>Thin Solid Films</i> , 1979 , 58, 61-66	2.2	14
1	Junction characteristics of Al-Al ₂ O ₃ -CdS diodes fabricated by molecular beam epitaxy. <i>Applied Physics Letters</i> , 1979 , 34, 413-415	3.4	2